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(54) Title: FRACTIONATED NOVOLAK RESIN AND PHOTORESIST COMPOSITION THEREFROM (57) Abstract The present invention provides a method for producing a film forming, fractionated novolak resin having consistent molecular weight and superior performance in photoresist composition, by isolating such novolak resin fractions without high temperature distillation. A method is also provided for producing photoresist composition from such a fractionated novolak resin and for producing semiconductor devices using such a photoresist composition.		